

ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of Invention

PLANARIZATION SYSTEM AND METHOD USING A
CARBONATE CONTAINING FLUID

Application Number :

Confirmation Number:

First Named Applicant: Donald Delehanty

Attorney Docket Number: FIS920020214







Art Unit:

Examiner:

Search string: (5968280 or 6294470 or 6350692 or 6358850 or 6468910 or 6485355 or
20020094649).pn


US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
	1	5968280	1999-10-19	Ronay			
	2	6294470	2001-09-25	Economikos et al.			
	3	6350692	2002-02-26	Economikos et al.			
	4	6358850	2002-03-19	Economikos et al.			
	5	6468910	2002-10-22	Economikos et al.			
	6	6485355	2002-11-26	Economikos et al.			

US Published Applications

Note: Applicant is not required to submit a paper copy of cited US Published Applications

init	Cite.No.	Pub. No.	Date	Applicant	Kind	Class	Subclass
	1	20020094649	2002-07-18	Arthanari et al.			

Signature

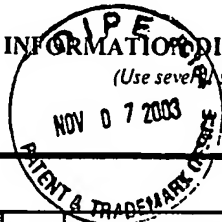


6-1-05

Examiner Name

Date

INFORMATION DISCLOSURE CITATION
(Use several sheets if necessary)



Docket Number (Optional) FIS9-2002-0214US1		Application Number 10/605,610
Applicant(s) Delehanty et al.		
Filing Date 10-13-03	Group Art Unit	

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

FOREIGN PATENT DOCUMENTS

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

		Appl. No. 60/463,358, Attorney Docket No. AMAT/7662L/CMP/CMP/RKK, entitled "Carbonation of ph controlled KOH solution for improved polishing of oxide films on semiconductor wafers"

EXAMINER 	DATE CONSIDERED 1-Aug-05
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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.